

Notice of References Cited	Application/Control No. 10/583,283	Applicant(s)/Patent Under Reexamination NAKANO ET AL.	
	Examiner Karuna P. Reddy	Art Unit 1713	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2006/0234154	10-2006	Nishimura et al.	430/270.1
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Computer translation: Nishimura et al, "(Meth)acrylic polymer and radiation-sensitive resin composition", July 29, 2004, JP-2004-210917.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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